

AMENDMENTS TO THE CLAIMS

A detailed listing of all claims that are, or were, in the present application, irrespective of whether the claim(s) remains under examination in the application are presented below. The claims are presented in ascending order and each includes one status identifier. Those claims not cancelled or withdrawn but amended by the current amendment utilize the following notations for amendment: 1. deleted matter is shown by strikethrough; and 2. added matter is shown by underlining.

1. (Original) A method of providing a pattern on a solid dosage form which comprises application of powder material in a pattern to a substrate, the method comprising the steps: providing a mask having an aperture between a source of the powder material and the substrate; applying the powder material to the substrate through the mask; effecting relative movement of the substrate with respect to the source of the powder material during the pattern application process.

2. (Original) A method according to claim 1 wherein the position of the mask is fixed relative to the source of the powder material and the substrate is moved past both the mask and the source of the powder material.

3. (Original) A method according to claim 1 wherein both the mask and the substrate are moved past the stationary source of the powder material.

4. (Currently Amended) A method according to ~~any preceding~~ claim 1 wherein the thickness of the mask is less than 2mm.

5. (Currently Amended) A method according to ~~any preceding~~ claim 1 wherein the mask is placed such that the surface of the substrate is less than 2mm from the surface of the mask during delivery of the powder material.

6. (Currently Amended) A method according to ~~any preceding~~ claim 1 wherein the aperture in the mask is round.

7. (Currently Amended) A method according to ~~any one of~~ claim[[s]] 1 [[to 6]] wherein the aperture in the mask is a slit whose length is along the direction of relative movement of the substrate.

8. (Currently Amended) A method according to ~~any one of~~ claim[[s]] 1 [[to 6]] wherein the aperture in the mask is a slit whose length is perpendicular to the direction of relative movement of the substrate.

9. (Currently Amended) A method according to ~~any one of~~ claim[[s]] 1 [[to 6]] wherein the aperture in the mask is a first slit intersected along its length by one or more further slits that extend transversely to the first slit.

10. (Currently Amended) A method according to ~~any preceding~~ claim 1 wherein the powder material is an electrostatically charged powder material applied by electrostatic means comprising applying a bias voltage to generate an electric field between the source of the powder material and the substrate; applying the electrostatically charged powder material to the substrate, the powder material being driven onto the substrate by the interaction of the electric field with the charged powder material.

11. (Original) A method according to claim 10 wherein the bias voltage is a DC voltage and powder is delivered continuously through the mask.

12. (Original) A method according to claim 10 wherein the bias voltage is a DC voltage in combination with a high frequency AC voltage and powder is delivered continuously through the mask.

13. (Original) A method according to claim 10 wherein the bias voltage is a low frequency AC voltage and powder is delivered periodically through the mask.

14. (Currently Amended) A method according to ~~any one of~~ claim[[s]] 10 [[to 13]] wherein the magnitude of the bias voltage is varied during application of the pattern.

15. (Original) A method according to claim 13 wherein the amplitude of the low frequency AC voltage is varied.

16. (Currently Amended) A method according to ~~any one of claim~~[[s]] 12, ~~13 or 14~~ wherein the frequency of the bias voltage is varied during application of the powder.

17. (Original) A method according to claim 14 wherein the voltage is varied as a constant polarity rectangular wave.

18. (Original) A method according to claim 14 wherein the voltage is varied as a constant polarity truncated triangular wave.

19. (Currently Amended) A method according to claim 17 [[or 18]] wherein the electrostatically charged powder material comprises two components, the particles of a first component being of one colour and one charge to mass ratio and the particles of a second component being of a different colour and a different charge to mass ratio, the charge to mass ratios being such that only the particles with the lower charge to mass ratio are driven onto the substrate when the voltage is at its lower value and both component particles are driven onto the substrate when the voltage is at its higher value.

20. (Currently Amended) A method according to ~~any preceding~~ claim 1 wherein the mask is made from an electrically insulating material.

21. (Currently Amended) A method according to ~~any one of claim~~[[s]] 10 [[to 20]] wherein the mask is made from an electrically conducting material.

22. (Original) A method according to claim 21 wherein the bias voltage between the source of the powder material and the substrate is a DC voltage and an AC or DC blocking voltage is applied to the conductive mask.

23. (Currently Amended) A method according to ~~any one of claim~~[[s]] 10 [[to 20]] wherein the mask has a matrix of dot apertures; the circumference of each aperture is electrically conductive; each conductive circumference is electrically insulated from the circumferences of the other dot apertures; and an AC or DC blocking voltage is used to individually address each circumference.

24. (Currently Amended) A method according to ~~any preceding~~ claim 1 further comprising a second application of powder material ~~by a method according to any one of claims 1 to 23.~~

25. (Original) A method according to claim 24 wherein the further powder material is applied only to areas of the substrate where powder was not applied in the first application.

26. (Currently Amended) A method according to ~~any preceding~~ claim 1 wherein the substrate to which the powder material is applied is the solid dosage form.

27. (Original) A method according to claim 26 wherein powder material is applied to a solid dosage form containing active material.

28. (Currently Amended) A method according to claim 26 [[or 27]] wherein powder material containing active material is applied to a solid dosage form.

29. (Currently Amended) A method according to ~~any one of~~ claim[[s]] 1 [[to 25]] wherein the powder material is applied to a substrate that is divisible into dosage unit forms.

30. (Currently Amended) A method according to ~~any preceding~~ claim 1 wherein the solid dosage form is an oral dosage form.

31. (Currently Amended) A method according to ~~any preceding~~ claim 1 wherein the solid dosage form is a pharmaceutical dosage form.

32. (Original) A method according to claim 31 wherein the pharmaceutical dosage form is a pharmaceutical tablet.

33. (Currently Amended) A method of applying powder material in a pattern to a pharmaceutical substrate that is divisible into unit dosage forms, the method comprising the steps: providing a mask having an aperture between a source of the powder material and a

pharmaceutical substrate; applying the powder material to the pharmaceutical substrate through the mask; and effecting relative movement of the pharmaceutical substrate with respect to both the source of powder material and the mask during the pattern application process; ~~and, if desired, dividing the pharmaceutical substrate into unit dosage forms.~~

34. (Original) An apparatus for providing a pattern on a solid dosage form by application of powder material in a pattern to a substrate, the apparatus including a source for powder material, a support assembly for supporting the substrate in the vicinity of the source of the powder material, a means for applying the powder material to the surface of the substrate, and a mask with an aperture, the apparatus being arranged such that, in use, the powder material is applied to the substrate through the aperture in the mask.

35. (Original) An apparatus as claimed in 34 wherein the mask is fixed relative to the source for powder material and the support assembly for the substrate is mounted for movement relative to both the mask and the source for powder material.

36. (Original) An apparatus as claimed in 34 wherein both the support assembly for the substrate and the mask are mounted for movement relative to the source for powder material.

37. (Currently Amended) An apparatus as claimed in ~~any one of claim~~[[s]] 34 [[to 36]] wherein the thickness of the mask is less than 2mm.

38. (Currently Amended) An apparatus as claimed in ~~any one of claim~~[[s]] 34 [[to 37]] wherein the mask is positioned such that the surface of the substrate is less than 2mm. from the surface of the mask during application of the powder material.

39. (Currently Amended) An apparatus as claimed in ~~any one of claim~~[[s]] 24 [[to 38]] wherein the aperture in the mask is round.

40. (Currently Amended) An apparatus as claimed in ~~any one of claim~~[[s]] 34 [[to 38]] wherein the aperture in the mask is a slit whose length is along the direction of movement of the substrate.

41. (Currently Amended) An apparatus as claimed in ~~any one of claim~~[[s]] 34 [[to 38]] wherein the aperture in the mask is a slit whose length is perpendicular to the direction of relative movement of the substrate.

42. (Currently Amended) An apparatus as claimed in ~~any one of claim~~[[s]] 34 [[to 38]] wherein the aperture is a first slit intersected along its length by one or more further slits that extend transversely to the first slit.

43. (Currently Amended) An apparatus as claimed in ~~any one of claim~~[[s]] 34 [[to 42]] wherein the source for powder material is a source for electrostatically charged powder material and the means for applying the powder material to the surface of the substrate comprises



a voltage source for applying a bias voltage between the source for the powder material and the substrate to generate an electric field therebetween, the apparatus being arranged such that, in use, the powder material is driven onto the substrate by the interaction of the electric field with the charged powder material.

44. (Original) An apparatus as claimed in claim 43 wherein the voltage source supplies a DC voltage.

45. (Original) An apparatus as claimed in claim 43 wherein the voltage source supplies a DC voltage in combination with a high frequency AC voltage.

46. (Original) An apparatus as claimed in claim 43 wherein the voltage source supplies a low frequency AC voltage.

47. (Currently Amended) An apparatus as claimed in ~~any one of claim~~[[s]] 43 [[to 46]] wherein the source for electrostatically charged powder material is a source for two-component powder material, the particles of a first component being of one colour and one charge to mass ratio and the particles of a second component being of a different colour and a different charge to mass ratio.

48. (Currently Amended) An apparatus as claimed in ~~any one of claim~~[[s]] 43 [[to 47]] wherein the mask is made from an electrically insulating material.

49. (Currently Amended) An apparatus as claimed in ~~any one of~~ claim 43 [[to 47]] wherein the mask is made from an electrically conducting material.

50. (Original) An apparatus as claimed in claim 49 wherein there is means for applying an AC or DC blocking voltage to the mask.

51. (Currently Amended) An apparatus as claimed in ~~any one of~~ claim[[s]] 43 [[to 47]] wherein the mask has a matrix of dot apertures; the circumference of each aperture is electrically conductive; each conductive circumference is electrically insulated from the circumferences of the other dot apertures; and means whereby an AC or DC blocking voltage individually addresses each circumference.

52. (Currently Amended) An apparatus as claimed in ~~any one of~~ claim[[s]] 34 [[to 51]] wherein wherein the substrate to which the powder material is applied is the solid dosage form and the support assembly is a support assembly for supporting a solid dosage form.

53. (Currently Amended) A solid dosage form that has had a pattern provided on it by a method according to ~~any one of~~ claim[[s]] 1 [[to 33]].